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NATHE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Kie T. Ahn et al. Examiner: David S. Blum

Serial No.: 09/945535 Group Art Unit: 2813

Filed: August 30, 2001 Docket: 1303.026US1

Title: HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXIDE ZRO2

## **COMMUNICATION CONCERNING RELATED APPLICATION(S)**

Mail Stop RCE Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Applicants would like to bring to the Examiner's attention the following related application(s) in the above-identified patent application:

Serial/Patent No. 09/944981	Filing Date Atto August 30, 2001	orney Docket 1303.021US1	Title CRYSTALLINE OR AMOPHOUS MEDIUM-K GATE OXIDES, Y203 AND Gd203
10/028643	December 20, 2001	1303.030US1	LOW-TEMPERATURE GROWN HIGH QUALITY ULTRA-THIN CoTiO3 GATE DIELECTRICS
10/052983	January 17, 2002	1303.031US1	HIGHLY RELIABLE AMORPHOUS HIGH-k GATE DIELECTRIC ZrOxNy
10/027315	December 20, 2001	1303.033US1	LOW-TEMPERATURE GROWN HIGH- QUALITY ULTRA-THIN PRASEODYMIUM GATE DIELECTRICS
10/099194	March 13, 2002	1303.044US1	EVAPORATION OF Y-Si-O FILMS FOR MEDIUM-k DIELETRICS
10/081439	February 20, 2002	1303.046US1	EVAPORATED LaAIO3 FILMS FOR GATE DIELECTRICS
10/137499	May 2, 2002	1303.050US1	ATOMIC LAYER-DEPOSITED LaAIO3 FILMS FOR GATE DIELETRICS

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Title: HIGHLY RELIAB	Title: HIGHLY RELIABLE AMORPHOUS HIGH-K GATE OXIDE ZROZ						
10/163481	June 5, 2002	1303.056US1	ATOMIC LAYER-DEPOSITED HFAIO3 FILMS FOR GATE DIELECTRICS				
10/163686	June 5, 2002	1303.059US1	Pr2O3-BASED La-oxide GATE DIELECTRICS				
10/209581	July 30, 2002	1303.061US1	ATOMIC LAYER DEPOSITED NANOLAMINATES OF HfO2/ZrO2 FILMS AS GATE DIELECTRICS				
10/219870	August 15, 2002	1303.069US1	LANTHANIDE DOPED TIOX DIELECTRIC FILMS BY PLASMA OXIDATION				
10/219878	August 15, 2002	1303.070US1	LANTHANIDE DOPED TiOx DIELECTRIC FILMS				
10/229903	August 28, 2002	1303.078US1	ATOMIC LAYER DEPOSITED HISION DIELECTRIC FILMS				
10/233309	August 29, 2002	1303.079US1	ATOMIC LAYER DEPOSITED LANTHANIDE DOPED TiOx DIELECTRIC FILMS				
10/309583	December 4, 2002	1303.082US1	ATOMIC LAYER DEPOSITED ZR-SN- TI-O FILMS USING TiI4				
10/309935	December 4, 2002	1303.083US1	ATOMIC LAYER DEPOSITED Zr-Sn-Ti-O FILMS				
10/379470	March 4, 2003	1303.090US1	ATOMIC LAYER DEPOSITED DIELECTRIC LAYERS				
10/403734	March 31, 2003	1303.092US1	ATOMIC LAYER DEPOSITED ZrAlxOy DIELECTRIC LAYERS				
10/420307	April 22, 2003	1303.097US1	ATOMIC LAYER DEPOSITED ZrTiO4 FILMS				
10/602323	June 24, 2003	1303.101US1	LANTHANIDE OXIDE / HAFNIUM OXIDE DIELECTRIC LAYERS				
10/602315	June 24, 2003	1303.107US1	LANTHANIDE OXIDE / HAFNIUM OXIDE DIELECTRICS				

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09/779959	February 9, 2001		External Matter
09/838335	April 20, 2001		External Matter
09/881408	June 13, 2001		External Matter
09/908767	July 18, 2001		External Matter
10/765619	January 27, 2004	1303.033US2	LOW-TEMPERATURE GROWN HIGH- QUALITY ULTRA-THIN PRASEODYMIUM GATE DIELECTRICS
	January 30, 2004	1303.033US3	LOW-TEMPERATURE GROWN HIGH- QUALITY ULTRA-THIN PRASEODYMIUM GATE DIELECTRICS
09/779959	February 9, 2001		External Matter
09/838335	April 20, 2001		External Matter
09/881408	June 13, 2001		External Matter
09/908767	July 18, 2001		External Matter

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Respectfully submitted,

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CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: Mail Stop RCE, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this 4th day of February, 2004.